

EAST - search notes

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	242	438/947.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/03 15:59
S2	138	438/950.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/03 16:12
S3	89	438/705.cor.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/03 16:19
S4	634	438/706.cor.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/03 16:42
S5	60	438/717.cor.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/03 16:55
S6	729	430/311.cor.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/03 16:58
S7	72	430/311.cor. and (nanostructure or microstructure or sub-lithograph\$3 or sublithograph\$3 or sub-resolut\$4 or subresolut\$4 or (mask or photoresist or resist) near3 (trim\$4) or fine near2 (lithograph\$3 or resolut\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/03 16:58
S8	521	430/313.cor.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/03 17:01
S9	143	(sublithograph\$4 or sub-lithograph\$4 or subresolut\$4 or sub-resolut\$4) near4 (lithography or photolithography or patterning)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/04 08:57
S10	39	(sublithograph\$4 or sub-lithograph\$4 or subresolut\$4 or sub-resolut\$4) near4 (lithography or photolithography or patterning) and (dopant or doping or impurity or boron or b or phosphorus or p or fluorine or f) near8 (etch or etching or etched or removal or removing or removed or trim or trimming or trimmed)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/03 17:05
S11	40	(dopant or doping or impurity) near3 (sensitive or selective or selectivity) near3 (etch or etching or patterning or trimming or trimmed or removal or removing) near8 (sidewall or ridge or edge or mask or photomask or pillar)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/04 09:17
S12	858	(dopant or doping or impurity) near2 (etch or etching or etchant or patterning or trimming or trimmed or removal or removing) near8 (sidewall or ridge or edge or mask or photomask or pillar)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/04 09:05

S13	209	(dopant or doping or impurity) near2 (etch or etching or etchant or patterning or trimming or trimmed or removal or removing) near8 (sidewall or ridge or edge or mask or photomask or pillar) and (semiconductor or silicon or si) and (resolution or resolving or lithograph\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/04 09:06
S14	59	(dopant or doping or impurity or boron or phosphorus or fluorine) near (sensitive or selective or selectivity or rate) near (etch or etching or patterning or trimming or trimmed or removal or removing) same (patterning or lithograph\$3 or photolithograph\$3 or resolution or resolving or photomask or hardmask or masking)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/04 09:19

Interference Text Search

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L2	55	((dopant or doping or impurity or boron or phosphorus or fluorine) near2 (etch or etching or trimming or trimmed or etched or patterned or patterning or lithography or lithographic) near15 (photomask or masking or mask)).clm.	US-PGPUB	OR	ON	2005/11/04 09:35
L3	82	((dopant or doping or impurity or boron or phosphorus or fluorine) near2 (surface or sidewall or side or wall or ridge or pillar or raised) near4 (etch or etching or trimming or trimmed or etched or patterned or patterning or lithography or lithographic or removal or removing)).clm.	US-PGPUB	OR	ON	2005/11/04 09:34
L6	3	((dopant or doping or impurity or boron or phosphorus or fluorine) near2 (surface or sidewall or side or wall or ridge or pillar or raised) near4 (etch or etching or trimming or trimmed or etched or patterned or patterning or lithography or lithographic or removal or removing) near15 (mask or masking or photomask)).clm.	US-PGPUB	OR	ON	2005/11/04 09:35
L7	5	((dopant or doping or impurity or boron or phosphorus or fluorine) near (sensitive or selective or selectivity or selectively) near (etch or etching or trimming or trimmed or etched or patterned or patterning or lithography or lithographic)).clm.	US-PGPUB	OR	ON	2005/11/04 09:36
L8	59	((sublithograph\$3 or sub-lithograph\$3 or sub-resuolt\$4 or subresolut\$4 or ultrafine or fine) near2 (patterning or patterned or lithograph\$3 or photolithograph\$4)).clm.	US-PGPUB	OR	ON	2005/11/04 09:37